

DOCKET: FI9-97-288

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

INVENTOR: C. Obszarny
SERIAL NO.: 09/216,395
FILING DATE: 16 July 1998

) EXAMINER: P. Kim
ART UNIT: 2851
DATE: 9 February 2000

FOR: APPARATUS AND METHOD FOR IN-SITU ADJUSTMENT OF
LIGHT TRANSMISSION IN A PHOTOLITHOGRAPHY PROCESSAMENDMENT

Assistant Commissioner of Patents
Washington, DC 20231

Dear Sir:

Responsive to the Office Action mailed 10 November 1999, please amend the application as follows:

In the Specification

On page 13, line 10, after "photo mask" add the following phrase: -- with polarizing SOG --.

On page 13, line 18, after "photo mask" delete the reference "26".

On page 13, line 18, after "polarized sections" add the reference -- 26 --.

On page 13, line 26, after "photo mask" add the following phrase: -- with polarizing SOG --.

On page 14, line 3, after "photo mask" add the following phrase: -- with polarizing SOG --.